3rd announcement

Celebrating 40 years

40th International Symposium on Dry Process (DPS2018)

November 13(Tue) – 15(Thu), 2018

Nagoya University, Nagoya, Aichi, Japan

The past, present, and future on dry process

40th Anniversary Program on November 13

International Symposium on Dry Process (DPS2018) will be held at Nagoya University, Nagoya in Japan, on November 13 to 15, 2018. The Symposium covers all aspects of the rapidly evolving fields of dry processes, including but not limited to plasma etching and deposition processes, diagnostics and modeling of plasmas and surfaces, and surface modifications by plasmas. The DPS has provided valuable forums for in-depth discussion among professionals and students working in this exciting field.

Free for registration fee of program on Nov.13

English simultaneous interpretation available

13:00 – 14:00

Atsuyoshi Koike (SanDisk and Western Digital Technologies, Inc.)

"Advanced Semiconductor Manufacturing – Intelligent Fab Systems and Smart Equipment"

14:00 – 14:30

Richard van de Sanden (The Eindhoven University of Technology (TU/e), the Netherland)

"Renewable energy driven non-equilibrium chemistry: plasma chemistry as the special case"

14:30 – 15:00

Hitoshi Wakabayashi (Tokyo Institute of Technology, Japan)

"Benchmark on Advanced Logic Devices and Predictive Discussion on Future LSIs"

15:00 – 15:30

Kanako Harada (JST/The University of Tokyo, Japan)

"Bionic Humanoids: current research and future vision"

15:30 – 16:00

Takayuki Morikawa (Nagoya University, Japan)

"Mobility Services with Autonomous Cars in Nagoya University COI Project"

Panel discussion 16:30 – 17:30

Challenges in industrial revolution (e.g. IoT, Energy, big data, artificial intelligence (AI), Mobility, Medicine, Robot, and the sharing economy) into social life.

Website: http://www.dry-process.org/2018/

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This year, we will invite very attractive state-of-the-art researchers at our main symposium in addition to the 40th anniversary special program day.

DPS2018 Invited Speakers on November 14 & 15

Required registration (charged)

Keynote speaker

Richard Gottscho (Lam Research Corp.) **9:40 – 10:20 AM, Nov. 14**

"Rethinking the Art of Etch"

Invited speakers

Arranged session: **A1. Control of surface reactions in atomic-precision plasma processing (ALE/ALD)**

Gottlieb S. Oehrlein (University of Maryland) **10:20 – 11:00 AM, Nov. 14**

"Materials Etching Selectivity in Plasma-Based Fluorocarbon Atomic Layer Etching (ALE) "

Emilie Despiau-Pujo (University of Grenoble Alpes) **11:20 – 12:00 AM, Nov. 14**

"Plasma solutions for atomic-precision etching: From atomistic simulations to experiments"

Silvia Armini (imec) **9:30 – 10:10 AM, Nov. 15**

"Area-selective deposition by surface engineering for applications in nanoelectronics. From blanket to confined dimensions."

Gert Leusink (Tokyo Electron U.S.) **10:10 – 10:50 AM, Nov. 15**

"Area Selective Processes for Advanced Devices: Challenges and Opportunities"

Arranged session: **A2. Etching challenges in extremely high-aspect-ratio (HAR) features (AR > 100)**

Sangwuk Park (Samsung Electronics Co., Ltd.) **15:10 – 15:50 PM, Nov. 15**

"Etching challenges in extremely high-aspect-ratio (HAR) features"

General session:

Nathan Marchack (IBM Corp.) **13:50 – 14:30 PM, Nov. 15**

"Towards Atomic Layer Etching of Metal Nitride Films: Understanding the Impact of Plasma Etch Parameters on Cyclic Etch Performance"

Yasuhiro Morikawa (ULVAC Inc.) **16:40 – 17:20 PM, Nov. 14**

"Plasma Dry Process Technology for Fan-out SiP"

For further general information, please contact: e-mail:dps2018@officepolaris.co.jp
Organizing Committee Chair: Keizo Kinoshita (AIO Core Co., Ltd.)
Executive Committee Chair: Masaru Hori (Nagoya University)
Program Committee Chair: Masanaga Fukasawa (Sony Semiconductor Solutions Corp.)
Publication Committee Chair: Tatsuo Ishijima (Kanazawa University)
Ad Hoc Committee Chair for 40th Anniversary Project: Kenji Ishikawa (Nagoya University)
On-line Registration: http://www.dry-process.org/2018/online_registration.html